

IN THE CLAIMS:

This listing of claims will replace all prior versions, and listings, of claims in the application. Please cancel claims 33-47 and 65:

Claims 1-32 (cancelled)

Claim 33-47 (cancelled)

Claim 48 (previously presented): A method for electroless deposition of nickel layers with internal compressive stresses from an electrolyte comprising a metal base salt, a reducing agent, a complexing agent, an accelerator, and a stabilizer; the method comprising depositing uniform metal layers at a steady high deposition rate of 7 to 12 $\mu\text{m/h}$ with a throughput of 14 to 22 MTO = 70 to 110 g metal/L; the metal base salt of the electrolyte being a metal salt whose anions are volatile and having an initial concentration of 0.048 to 0.105 mol/L.

Claim 49 (previously presented): The method of claim 48, wherein the metal salts whose anions are volatile is selected from the group consisting of the acetates, formates, oxalates, propionates, citrates or ascorbates, or any combination thereof.

Claim 50 (previously presented): The method of claim 48, wherein the metal is selected from the group consisting of nickel, copper, silver or gold.

Claim 51 (previously presented): The method of claim 48, wherein a makeup solution is added to the electrolyte while practicing the method.

Claim 52 (previously presented): The method of claim 51, wherein the makeup solution comprises a reducing agent, an alkaline-buffered complexing agent, and an accelerator.

Claim 53 (previously presented): The method of claim 51, wherein a second makeup solution is added to the electrolyte while practicing the method.

Claim 54 (previously presented): The method of claim 53, wherein the second makeup solution comprises a nickel base salt, a complexing agent, an accelerator, and a stabilizer.

Claim 55 (previously presented): The method of claim 48, the method being carried out with a closed material circulation.

Claim 56 (previously presented): The method of claim 48, the method being used to co-deposit additional materials, the additional materials being selected from the group consisting of phosphorus, metals, cobalt, and finely divided particles, or any combination thereof.

Claim 57 (previously presented): The method of claim 56, the method being used to deposit metal-phosphorus layers with phosphorus contents >10%.

Claim 58 (previously presented): The method of claim 56, the method being used to deposit metal-phosphorus layers with phosphorus contents from 2-10%, and wherein electrolyte has a pH between 4.6-6.2.

Claim 59 (previously presented): The method of claim 48, wherein the reducing agent is sodium hypophosphite.

Claim 60 (previously presented): The method of claim 48, wherein the complexing agent is selected from the group consisting of carboxylic acids, polycarboxylic acids, their salts, their derivatives, hydroxy(poly)carboxylic acids, 2-hydroxypropanoic acid, and propandioic acid, or any combination thereof.

Claim 61 (previously presented): The method of claim 48, wherein the complexing agent has a concentration between 70 g/L to 90 g/L.

Claim 62 (previously presented): The method of claim 48, wherein the accelerator is a sulfur-containing heterocycle.

Claim 63 (previously presented): The method of claim 62, wherein the sulfur-containing heterocycle is selected from the group consisting of saccharine, saccharine salts, saccharine derivatives, and sodium saccharate, or any combination thereof.

Claim 64 (previously presented): The method of claim 48, wherein the electrolyte is regenerated by means of electrodialysis or ion exchange resins, or a combination thereof.

Claim 65 (cancelled).